

<b>Form PTO-1449 (modified)</b>  <b>List of Patents and Publications for Applicant's</b>  <b>INFORMATION DISCLOSURE STATEMENT</b>  (Use several sheets if necessary)	<b>Atty. Docket No.</b> 102-0090US-C	<b>Serial No.</b> unk
	<b>Inventor/Applicant:</b> Christophe Pierrat et al./ Micron Technology, Inc.	
	<b>Title: PROCESS FOR DETECTING DEFECTS IN PHOTOMASKS</b>	
	<b>Filing Date:</b> herewith	<b>Group:</b>

### U.S. Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Name	Class	Sub Class	Filing Date of App.
BL	A1	4,633,504	12-30-86	Mark J. Wihl			6-28-84
	A2	4,926,489	5-15-90	Danielson, et al.			10-05-87
	A3	5,563,702	10-08-96	Emery, et al.			7-13-94
	A4	5,795,688	8-18-98	Burdorf, et al.			8-14-96
	A5	6,064,484	5-16-00	Kobayashi, et al.			3-11-97
	A6	4,527,070	7-02-85	Matsui, et al.			8-20-82
	A7	5,850,467	12-15-98	Matsui, et al.			11-15-94
	A8	5,029,222	7-02-91	Yamada, et al.			8-30-88
	A9	4,809,341	2-28-89	Matsui, et al.			7-13-87
	A10	5,307,421	4-26-94	Darboux, et al.			10-14-92
	A11	5,804,340	9-08-98	Garza, et al.			12-23-96
	A12	5,481,624	1-02-96	Kazuya Kamon			4-13-93
	A13	5,475,766	12-12-95	Tsuchiya, et al.			9-04-92
	A14	5,379,348	1-03-95	Watanabe, et al.			3-31-93
	A15	5,048,093	9-10-91	Kimura, et al.			4-11-90
	A16	5,306,585	4-26-94	Yoshihiko Okamoto			4-23-93
	A17	4,644,172	2-17-87	Sandland, et al.			2-22-84
	A18	5,129,009	7-07-92	Christopher J. Lebeau			6-04-90
	A19	4,893,346	1-09-90	Robert Bishop			9-02-87
	A20	5,707,765	1-13-98	Chen			5-28-96
	A21	5,725,974	3-10-98	Kawahira			6-28-96
BL	A22	5,441,834	8-15-95	Takekuma			9-10-92

<b>EXAMINER:</b> <i>Burke</i>	<b>DATE CONSIDERED:</b> 05/21/07
<small>EXAMINER: INITIAL IF REFERENCE CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED. INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.</small>	

Form PTO-1449 (modified)	Atty. Docket No. 102-0090US-C	Serial No. unk	2
List of Patents and Publications for Applicant's  INFORMATION DISCLOSURE STATEMENT  (Use several sheets if necessary)	Inventor/Applicant: Christophe Pierrat et al./ Micron Technology, Inc.		
	Title: <b>PROCESS FOR DETECTING DEFECTS IN PHOTOMASKS</b>		
	Filing Date: herewith	Group:	

### U.S. Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Name	Class	Sub Class	Filing Date of App.
BL	A23	5,125,040	6-23-92	Matsui	/	/	9-24-90
BL	A24	5,862,058	1-19-99	Samuels et al.	/	/	5-16-96
BL	A25	5,849,440	12-15-98	Lucas et al.	/	/	1-29-97

### Foreign Patent Documents

Exam. Init.	Ref. Des.	Document Number	Publication Date	Country	Class	Sub Class	Translation Yes/No
BL	B1	0485274A2	5-13-92	Europe	/	/	Yes
BL	B2	138639	Apr. 1995	Europe	/	/	Yes

### Other Art (Including Author, Title, Date Pertinent Pages, Etc.)

Exam. Init.	Ref. Des.	Citation
BL	C1	S. Takeuchi, et al., "Advanced 5x reticle inspection technologies for ULSI devices," Integrated Circuit Metrology, Inspection, and Process Control IV, Vol. 1261, 1990, pp. 195-205.
BL	C2	Splat v5.0 Users' Guide (U. California Berkeley) (Jan. 19, 1995).
BL	C3	S. Wolf et al., "Silicon Processing," Vol. 1, Lattice Press, pg. 483-485.

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05/21/07

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